

Attorney's Docket No.:10559-927001

Amendment to the Claims:

This listing of claims replaces all prior versions, and listings, of claims in the application:

1.-9. (Cancelled)

10. (Currently Amended) ~~The system of claim 9, A~~
lithography system, comprising:

a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator,

wherein the stress modulator is configured to apply stress to an outer surface of the polarization modulator to obtain a polarization profile at an imaging plane

wherein the polarization profile exhibits substantially azimuthal symmetry.

11. (Cancelled)

12. (Currently Amended) ~~The system of claim 1, A~~
lithography system, comprising:

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a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator, wherein the lithography system comprises an immersion lithography system.

13. (Cancelled)

14. (Currently Amended) ~~The system of claim 1, A~~
lithography system, comprising:

a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator, wherein the stress modulator is configured to apply stress using expansion.

15. (Currently Amended) ~~The system of claim 1, A~~
lithography system, comprising:

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a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator, wherein the stress modulator is configured to apply stress by heating at least one of the stress modulator and the polarization modulator.

16. (Currently Amended) ~~The system of claim 1, A~~
lithography system, comprising:

a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator, wherein the stress modulator is configured to apply stress by cooling at least one of the stress modulator and the polarization modulator.

17. (Currently Amended) ~~The system of claim 1, A~~
lithography system, comprising:

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a polarization modulator configured to change light which is applied thereto from a first polarization profile to a second polarization profile different than the first polarization profile; and

a stress modulator in communication with the polarization modulator, the stress modulator to apply stress to the polarization modulator, further comprising:

another polarization modulator positioned to receive light having a received polarization profile and to transmit light having a different transmitted polarization profile; and

another stress modulator in communication with the another polarization modulator, the another stress modulator to apply stress to the another polarization modulator.

18.-23. (Cancelled)

24. (Currently Amended) ~~The method of claim 22,~~ A method of modifying the polarization of light, comprising:

applying stress to a polarization modulator;

receiving light of a first polarization state in the polarization modulator;

modifying the polarization of light within the polarization modulator; and

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transmitting light of a second polarization state different than the first polarization state from the polarization modulator, wherein the parameter is related to the second polarization state.

25. (Currently Amended) ~~The method of claim 22,~~ A method of modifying the polarization of light, comprising:
applying stress to a polarization modulator;
receiving light of a first polarization state in the polarization modulator;
modifying the polarization of light within the polarization modulator; and
transmitting light of a second polarization state different than the first polarization state from the polarization modulator wherein the parameter is related to the second polarization state;
~~further comprising~~ forming a pattern on a substrate using the transmitted light, and wherein the parameter is a parameter based on the pattern.

26.-28. (Cancelled)

29. (Currently Amended) ~~The system of claim 28,~~ The system of claim 26, further including a light sensor positioned to

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receive at least a portion of the transmitted light, the light sensor in communication with the controller wherein the signal based on the parameter is a signal from the light sensor;

wherein the parameter is based on the second different polarization profile.

30. (Currently Amended) ~~The system of claim 26,~~ The system of claim 27, wherein the signal based on the parameter is a signal from the light sensor further comprising a substrate including a pattern formed using the transmitted light, and wherein the parameter is based on the pattern.